

SUBSTRATE PROCESSING APPARATUS AND ELECTROSTATIC CHUCK

ABSTRACT

An electrostatic chuck includes: an upper surface, and a chuck main body having at least one first gas supply path and at least one second gas supply path, in which protrusions, a first annular groove, a second annular groove surrounding the first annular groove, and an annular projection disposed between the first annular groove and the second annular groove, protruding from the upper surface, and lower than the protrusions are formed on the upper surface, the first annular groove communicates with the at least one first gas supply path via at least one first gas supply hole, and the second annular groove communicates with the at least one second gas supply path via at least one second gas supply hole.

Figure 5